

Development Project of “New Mo Precursors” Ver.2

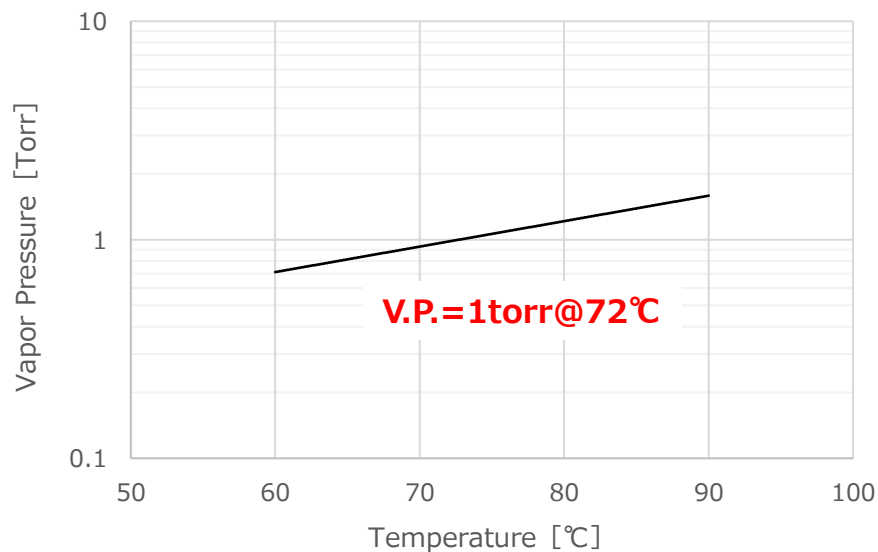
□ Target

- MoO_x
- Mo_xN_y
- Mo metal

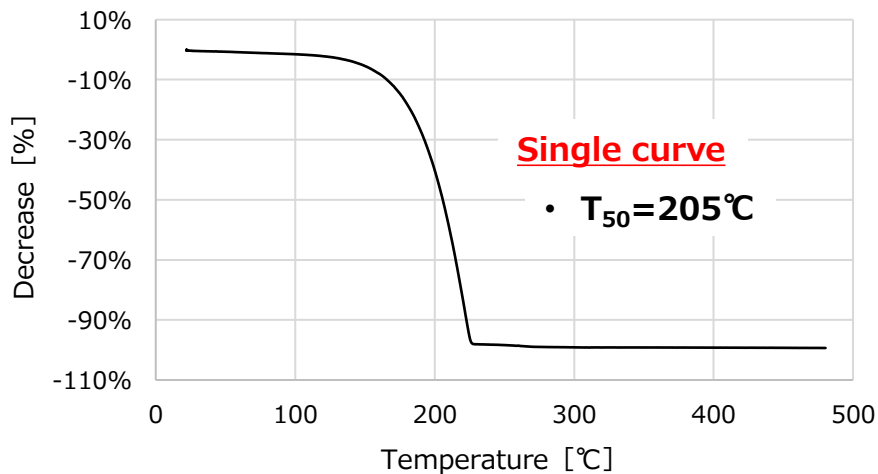
□ New Mo Precursor

- Code Name : [TCMo-19](#)
- Physical State : [Liquid](#)

[V.P. curve]



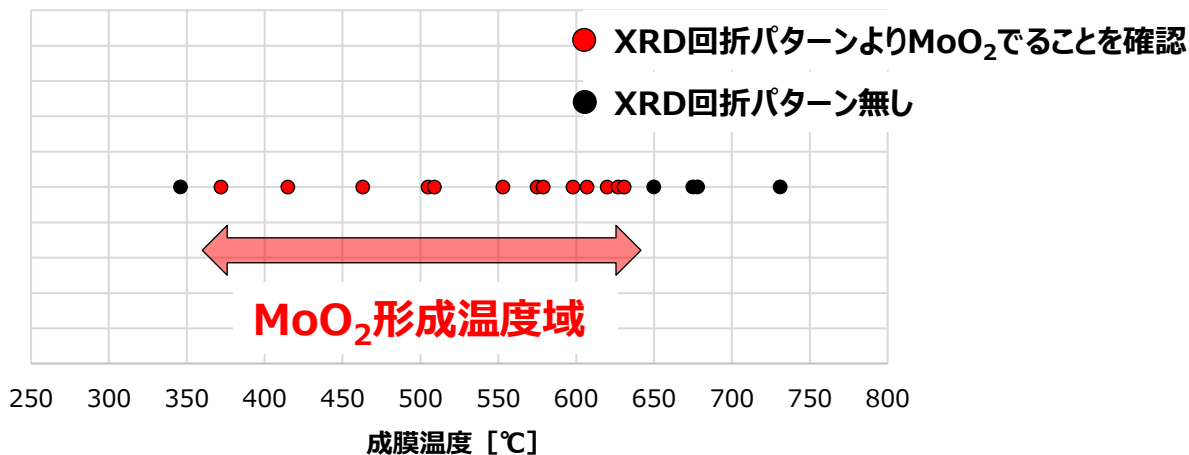
[TG-DTA]



□ Result (1)

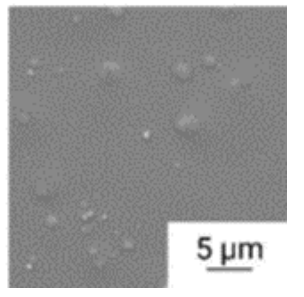
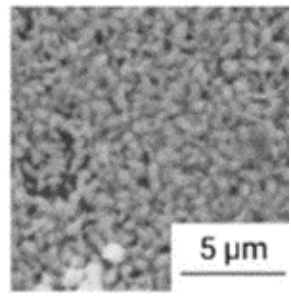
- レーザーCVD
- MoO₂

成膜温度比較	Reactant O ₂ / (100)Si ; MoO ₂	
成膜温度	415°C	620°C
XRD Patterns		



□ Result (2)

- レーザーCVD
- MoO₃

	As Depo.	After annealed
条件	375°C / 10min	600°C / 3hr
組成	MoO ₂	MoO ₃
表面SEM画像		

[XRD回折パターン]

